

## Thin Film Processing and Devices (TF)

### Oral Presentation

Nov. 7, 2011 (Mon.)

#### TF 1 (Thin Film Processing and Devices 1)

Ara

Chair: Prof. Migaku Takahashi (Tohoku University, Japan)

15:00-16:10

- TF1S1** **Biaxial Texturing of CeO<sub>2</sub> Buffer Layer on the MgO Substrates by Pulsed Laser Deposition**  
15:00-15:30 Ara  
Invited Speech Sang-Im Yoo  
*Seoul National University, Korea*

- TF1159** **SiGe Synthesis by Ge Ion Implantation**  
15:30-15:50 Hyunng-Sang Yuk<sup>1</sup>, Tom Tate<sup>1</sup>, Kristel Fobelets<sup>1</sup>, Jin-Heon Oh<sup>2</sup>, Kee-Joe Lim<sup>2</sup>  
<sup>1</sup>*Imperial College London, UK*, <sup>2</sup>*Chungbuk National University, Korea*

- TF649** **Electrical Properties of Nano-Floating Gate Memory with Bi Nanocrystals Embedded in Bi<sub>2</sub>Mg<sub>2/3</sub>Nb<sub>4/3</sub>O<sub>7</sub> (BMM) Thin Films**  
15:50-16:10 Hyun-June Jung, Hyun-A Song, Seung-Dong Yang, Kwang-Seok Jeong, Ga-Won Lee, Soon-Gil Yoon  
*Chungnam National University, Korea*

Nov. 7, 2011 (Mon.)

#### TF 2 (Thin Film Processing and Devices 2)

Ara

Chair: Prof. Migaku Takahashi (Tohoku University, Japan)

16:30-17:50

- TF1599** **Structural and Electrical Properties of Bi<sub>2</sub>O<sub>3</sub>-Nb<sub>2</sub>O<sub>5</sub> Thin Film Grown on Pt/Ti/SiO<sub>2</sub>/Si Substrate at Low Temperature for Embedded Capacitors**  
16:30-16:50 Ara  
Jin-Seong Kim, Jong-Woo Sun, Sahn Nahm  
*Korea University, Korea*

- TF1294** **Super-filling of High Aspect-Ratio Features with Copper by Catalyst Enhanced CVD Coupled with Plasma Treatment and its Modeling**  
16:50-17:10 Won-Jong Lee, Chang-Gyu Kim  
*KAIST, Korea*

- TF637** **Nanocrystalline/Nanocolumnar Aluminum Thin Film Electrode for Li-ion Rechargeable Batteries**  
17:10-17:30 Ara  
S K Sharma<sup>1,2</sup>, Bo-Gyun Kim<sup>1</sup>, Min-Sik Kim<sup>3</sup>, Jong-Sung Yu<sup>3</sup>, Chi Kyu Choi<sup>2</sup>  
<sup>1</sup>*Cheju Halla College, Korea*, <sup>2</sup>*Jeju National University, Korea*, <sup>3</sup>*Korea University, Korea*

- TF513** **Bandgap Alteration of Transparent Zinc Oxide Thin Film with Mg Dopant**  
17:30-17:50 Salina Muhamad, Suriani Abu Bakar, Rafidah Ahmad, Mohamad Hafiz Mamat, Mohamad Rusop Mahmood  
*Universiti Teknologi MARA, Malaysia*

Nov. 8, 2011 (Tue.)

**TF 3 (Thin Film Processing and Devices 3)**

Ara

Chair: Dr. Cong Wang (Kwangwoon University, Korea)

09:10-10:20

**TFIS2 Atomically Controlled Processing for Oxide Thin Films and Nanowires**

09:10-09:40 Tomozi Kawai

Invited Speech *Osaka University, Japan, Konkuk University, Korea***TF298 The Electrical Characterization of Post-annealed ZnO TFTs as a Function of Different Temperature Under O<sub>2</sub> Ambient**09:40-10:00 Kwang Seok Jeong<sup>1</sup>, Yu Mi Kim<sup>1</sup>, Ho Jin Yun<sup>1</sup>, Seung Dong Yang<sup>1</sup>, Sang Youl Lee<sup>1</sup>, Young Su Kim<sup>2</sup>, Hi Deok Lee<sup>1</sup>, Ga Won Lee<sup>1</sup><sup>1</sup>*Chungnam National University, Korea,* <sup>2</sup>*National Nanofab Center, Korea***TF267 Indium Tin Oxide Thin Films Crystallized at a Low Temperature on Polymer Substrate by Off-axis RF Magnetron Sputtering**

10:00-10:20 Hyung-Jin Choi, Hyun-June Jung, Soon-Gil Yoon

*Chungnam National University, Korea*

Nov. 8, 2011 (Tue.)

**TF 4 (Thin Film Processing and Devices 4)**

Ara

Chair: Prof. Sang Im Yoo (Seoul National University, Korea)

10:40-12:00

**TF582 The Impact of High-pressure Oxygen Annealing on Negative Bias Illumination Stress-induced Instability of ZnSnO Thin Film Transistors**10:40-11:00 Kwang Hwan Ji<sup>1</sup>, Ji-In Kim<sup>1</sup>, Hong Yoon Jung<sup>1</sup>, Se Yeob Park<sup>1</sup>, Shinhuk Yang<sup>2</sup>, Un Ki Kim<sup>3</sup>, Cheol Seong Hwang<sup>3</sup>, Sang-Hee Ko Park<sup>2</sup>, Chi-Sun Hwang<sup>2</sup>, Jae Kyeong Jeong<sup>1</sup><sup>1</sup>*Inha University, Korea,* <sup>2</sup>*Electronics and Telecommunications Research Institute, Korea,*<sup>3</sup>*Seoul National University, Korea***TF572 High Performance ZnSnO Transistors by Inserting Ultra-thin InSnO Layer at the Gate Insulator/channel Interface**11:00-11:20 Ji-In Kim, Kwang Hwan Ji, Hong Yoon Jung, Se Yeob Park, Jae Kyeong Jeong  
*Inha University, Korea***TF904 Electrical Instabilities in a-InGaZnO Thin Film Transistors with Si<sub>3</sub>N<sub>4</sub> and Si<sub>3</sub>N<sub>4</sub>/Al<sub>2</sub>O<sub>3</sub> Gate Dielectrics**11:20-11:40 Yu-Mi Kim, Kwang-Seok Jeong, Ho-jin Yun, Seung-Dong Yang, Sang-Youl Lee, Hi-Deok Lee, Ga-won Lee  
*Chungnam National University, Korea*

## Thin Film Processing and Devices

- TF895** **The Optimization of Photoconductors in the Fabrication of X-ray Conversion Materials by the Physical and Chemical Treatments for the Stability and Reproducibility of Digital X-ray Film**

11:40-12:00 Kyung-Min Oh<sup>1</sup>, Jung-Wook Shin<sup>1</sup>, Young-Gyu Lee<sup>1</sup>, Yong-Gyun Song<sup>1</sup>, Sung-Gwang Park<sup>2</sup>, Sang-hee Nam<sup>1</sup>

<sup>1</sup>Inje University, Korea, <sup>2</sup>Busan Paik Hospital, Korea

Nov. 8, 2011 (Tue.)

### TF 5 (Thin Film Processing and Devices 5)

Ara

Chair: Prof. Tomoji Kawai (Osaka University, Japan)

15:30-16:40

- TF1S3** **Iron-Nitride Compound as a New Candidate for Future Permanent Magnetic Material**

15:30-16:00 Invited Speech  
Migaku Takahashi  
*Tohoku University, Japan, Chungnam National University, Korea*

- TF271** **Tunable Magnetism by Magnetic Phase in Fe<sub>3</sub>O<sub>4</sub>/ZnO Multilayer**

16:00-16:20 Jong-Gu Yun<sup>1</sup>, Chang-Yup Park<sup>2</sup>, Soon-Gil Yoon<sup>1</sup>  
<sup>1</sup>*Chungnam National University, Korea*, <sup>2</sup>*Korea Advanced Institute of Science and Technology, Korea*

- TF261** **Characterization of the Bi<sub>2</sub>Mg<sub>2/3</sub>Nb<sub>4/3</sub>O<sub>7</sub>(BMNO)-Bi Nanostructured Thin Films Grown at Room Temperature by RF-sputtering**

16:20-16:40 Hyun-A Song, Hyun-June Jung, Soon-Gil Yoon  
*Chungnam National University, Korea*

Nov. 8, 2011 (Tue.)

### TF 6 (Thin Film Processing and Devices 6)

Ara

Chair: Dr. Hyungsang Yuk (University of Texas at Dallas, USA)

17:00-18:20

- TF1219** **Microwave Plasma Reactor for Diamond Thin Film Device Fabrication**

17:00-17:20 B. Paosawatanyong<sup>1,2</sup>, N. Ruijsamphan<sup>1</sup>, W. Bhanthumnavin<sup>1</sup>  
<sup>1</sup>*Chulalongkorn University, Thailand*, <sup>2</sup>*Commission on Higher Education, Thailand*

- TF149** **Epitaxy of Cu Thin Films on  $\alpha$ -Al<sub>2</sub>O<sub>3</sub> (0001) by Electron Beam Evaporation**

17:20-17:40 Sung-Jae Joo, Wook Bahng  
*Korea Electrotechnology Research Institute, Korea*

- TF109** **Effects of SU-8-based Thin Film for Various Microelectronic Applications**

17:40-18:00 Cong Wang, Won-Sang Lee, Nam-Young Kim  
*Kwangwoon University, Korea, Nano ENS Inc., Korea*

**TF305 Structural, Electrical and Optical Properties of  $\gamma$ -sprayed Cu Thin Films**

18:00-18:20 M.N. Amalina, M.Rusop  
*Universiti Teknologi MARA (UiTM), Malaysia*

Nov. 10, 2011 (Thu.)

**TF 7 (Thin Film Processing and Devices 7)**

Ara

Chair: Prof. Zonghoon Lee (Ulsan National Institute of Science and Technology, Korea)

09:10-10:20

**TFIS4 Using Visible Light to Enhance the Photo-response Switching of Flexible CdS Films**

09:10-09:40 Sung-Gi Hur<sup>1</sup>, Hyung-Jin Choi<sup>1</sup>, Jeong-Sun Kim<sup>2</sup>, Geun-Hong Kim<sup>2</sup>, Soon-Gil Yoon<sup>1</sup>  
<sup>1</sup>Chungnam National University, Korea, <sup>2</sup>Agency for Defense Development, Korea

**TF422 The Influences of Gate-bias and Light Stresses on Device Characteristics of High-energy Electron Beam Irradiated IGZO-based TFTs**

09:40-10:00 Kyeong Min Yu<sup>1</sup>, Hye Ji Moon<sup>1</sup>, Min Ki Ryu<sup>2</sup>, Kyoung Ik Cho<sup>2</sup>, Eui-Jung Yun<sup>1</sup>, Byung Seong Bae<sup>1</sup>  
<sup>1</sup>Hoseo University, Korea, <sup>2</sup>ETRI, Korea

**TF1323 High Benefit Performance via a Safety Mechanism of a Non-contact Module on Optical Device Surfaces**

10:00-10:20 P.S. Pa  
*National Taipei University of Education, Taiwan*

Nov. 10, 2011 (Thu.)

**TF 8 (Thin Film Processing and Devices 8)**

Ara

Chair: Prof. Soon-Gil Yoon (Chungnam National University, Korea)

10:40-12:10

**TFIS5 Investigation on Grain Boundaries in Monolayer Graphene by Advanced TEM**

10:40-11:10 Zonghoon Lee<sup>1</sup>, Kwanpyo Kim<sup>2</sup>, W. Regan<sup>2</sup>, M. Crommie<sup>2</sup>, A. Zettl<sup>2</sup>  
<sup>1</sup>UNIST, Korea, <sup>2</sup>UC Berkeley, USA

**TF234 Electrode Applications of the Transparent Capacitors Through an Optimal Patterning of the Graphene**

11:10-11:30 Sin-Hye Na, Hyun-A Song, Sung-Gi Hur, Soon-Gil Yoon  
*Chungnam National University, Korea*

**TF795 Analytical Study on Femtosecond Laser Processing for Au Films**

11:30-11:50 Ching-Yen Ho, Yu-Hsiang Tsai, Jing-Yi Lv, Mao-Yu Wen  
*Hwa-Hsia Institute of Technology, Taiwan*

## Thin Film Processing and Devices

- TF419** **Research on the Characteristics of Dielectric Barrier Discharge and Dielectric Barrier Corona Discharge**  
11:50-12:10 Mi Zeng, Zhiyong Cui, Yan-zhou Sun  
*Henan Polytechnic University, China*

### Poster Presentation

Nov. 7, 2011 (Mon.)

- TFP 1 (Thin Film Processing and Devices) Poster Presentation 1** Lobby 8F  
Chair: Prof. Soon-Gil Yoon (Chungnam National University, Korea) 13:30-15:00

- TF1633** **Deposition of ZnO Thin Films by MOCVD using Ultrasonic Nebulization**  
Choon-Ho Lee  
*Keimyung University, Korea*
- TF1632** **Preparation of Al Doped ZnO Thin Films by MOCVD using Ultrasonic Nebulization**  
Do-Woo Kim, Choon-Ho Lee  
*Keimyung University, Korea*
- TF1613** **Effect of Electron Irradiation on the Electrical/Optical Properties in Nanostructured Oxide Thin Films**  
Chan-Rok Park, Woo-Ri Do, Dai-Hui Cho, Da-Gam Bae, Jin-Ha Hwang  
*Hongik University, Korea*
- TF1585** **The Effect of the Interfacial Properties between Channel Layer and Gate Insulator on the Electrical Performance of In-Ga-Zn Oxide Thin Film Transistor**  
Bosul Kim<sup>1,2</sup>, Do Hyung Kim<sup>1,3</sup>, Sang Yeol Lee<sup>1</sup>  
<sup>1</sup>Korea Institute of Science and Technology, Korea, <sup>2</sup>University of Science & Technology, Korea, <sup>3</sup>University of Dongguk, Korea
- TF1554** **The PL Characteristics of ZnO Thin Film on Flexible Polymer Substrate by Pulse Laser Deposition with Various Temperatures**  
Cheon Lee, Young Jin Choi  
*Inha University, Korea*
- TF1511** **Thermal Design and Annealing Effects on the VOx Device for Uncooled IR Microbolometer**  
Myung-Soo Han<sup>1</sup>, Il-Mong Park<sup>1</sup>, Seok-Man Han<sup>1</sup>, Hang-Ju Ko<sup>1</sup>, Hyo-Jin Kim<sup>1</sup>, Sung-Gap Lee<sup>2</sup>  
<sup>1</sup>Korea Photonics Technology Institute, Korea, <sup>2</sup>Gyeongsang National University, Korea

- TF1503 High Mobility P-Channel Thin-film Transistors with Ultra-Large Grain Poly-Si Formed using Nickel Induced Crystallization**  
 Kyungsoo Jang, Wonbaek Lee, Kyunghyun Baek, Woojin Choi, Junsin Yi  
*Sungkyunkwan University, Korea*
- TF1470 Pulsed DC Bias Effects on p-type Semiconductor SrCu<sub>2</sub>O<sub>2</sub> Film Deposited by RF Magnetron Sputtering**  
 Hye-Won Seok<sup>1,2</sup>, Sei-Ki Kim<sup>1</sup>, Hyun-Seok Lee<sup>1</sup>, Mi-Jae Lee<sup>1</sup>, Byeong-Kwon Ju<sup>2</sup>  
<sup>1</sup>Korea Institute of Ceramic Engineering and Technology (KICET), Korea, <sup>2</sup>Korea University, Korea
- TF1448 Investigation of Thin Metal Sheet via Continuous Strip Casting**  
 Changbum Lee<sup>1</sup>, Jaewoo Lee<sup>1</sup>, Bo-Yun Jang<sup>2</sup>, Joonsoo Kim<sup>2</sup>, Youngsoo Ahn<sup>2</sup>  
<sup>1</sup>Korea University, Korea, <sup>2</sup>Korea Institute of Energy Research, Korea
- TF1433 Morphology Properties of SnO<sub>2</sub> Thin Films Fabricated by using E-beam Method**  
 Chang Hoon Sung<sup>1</sup>, Geun Woo Kim<sup>1</sup>, Keun Young Park<sup>1</sup>, Yong Jun Seo<sup>1</sup>, Sung Hun Lee<sup>2</sup>, Eung Sun Byon<sup>2</sup>, Nam Jin Lyu<sup>3</sup>, Bon Heun Koo<sup>1</sup>  
<sup>1</sup>Changwon National University, Korea, <sup>2</sup>Korea Institute of Materials Science (KIMS), Korea, <sup>3</sup>Kang Nam Co. Ltd, Korea
- TF1425 Effect of Dopants(Tri-valent, Penta-valent) on the Electrical and Optical Properties of SnO<sub>2</sub> based Transparent Electrodes**  
 Bon Heun Koo<sup>1</sup>, Yong Jun Seo<sup>1</sup>, Geun Woo Kim<sup>1</sup>, Chang Hoon Sung<sup>1</sup>, Keun Young Park<sup>1</sup>, Byung Hyun Ahn<sup>1</sup>, Si Nae Heo<sup>1</sup>, M. S. Anwar<sup>1</sup>, Sung Hun Lee<sup>2</sup>, Eung Sun Byon<sup>2</sup>, Nam Jin Lyu<sup>3</sup>  
<sup>1</sup>Changwon National University, Korea, <sup>2</sup>Korea Institute of Materials Science (KIMS), Korea, <sup>3</sup>Kang Nam Co. Ltd, Korea
- TF1419 A Mask Aligner System Utilizing Photolithography for Applying Liquid Crystal Mask as a Photomask**  
 Min Sup Oh<sup>1</sup>, Chang Kyo Kim<sup>1</sup>, Jae Hong Lee<sup>2</sup>, Chinsoo Hong<sup>1</sup>  
<sup>1</sup>Soonchunhyang University, Korea, <sup>2</sup>NST Co. Ltd., Korea
- TF1418 Transparent Properties of p-type Conducting Sb<sub>2</sub>O<sub>3</sub> Doped SnO<sub>2</sub> Thin Films by Pulsed Laser Deposition**  
 Keun-Young Park, Geun-Woo Kim, Yong-Jun Seo, Chang-Hoon Sung, Si-Nae Heo, Bon Heun Koo  
*Changwon National University, Korea*
- TF1413 Transparent p-type Conducting Al/SnO<sub>2</sub>/Al Multilayer Thin Films Deposited by Sputtering**  
 Geun Woo Kim, Keun Young Park, Chang Hoon Sung, Yong Jun Seo, Tae Kwon Song, Bon Heun Koo  
*Changwon National University, Korea*

## Thin Film Processing and Devices

- TF1325 Mn-doping Effect on Resistive Switching Characteristics of Zinc Oxsulfide Thin Films on Plastic Substrates**  
Yong Han, Kyoungah Cho, Sangsig Kim  
*Korea University, Korea*
- TF1319 Experimental Study on Discharge Characteristics of MgO Layer with MgO Single Crystal Powder in AC-PDPs**  
Jae Hyun Kim, Coon-Sang Park, Hyung-Dal Park, Heung-Sik Tae  
*Kyungpook National University, Korea*
- TF1317 Investigation of Discharge Characteristics and Efficiency by Thickness of Phosphor Layer in Plasma Display Panel**  
Hyung Dal Park, Jae Hyun Kim, Choon-Sang Park, Heung-Sik Tae  
*Kyungpook National University, Korea*
- TF1310 Influence of Surface and Plate-Gap Discharges on Panel-Aging Characteristics in AC Plasma Display Panel**  
Choon-Sang Park, Heung-Sik Tae  
*Kyungpook National University, Korea*
- TF1301 Investigation of the Addition of Vanadium into In-Ga-Zn Oxide Thin Film Transistor Fabricated by Solution Process**  
Jun Young Choi<sup>1,2</sup>, Ki-Ho Park<sup>1</sup>, Yun su Jun<sup>1</sup>, Sang Sig Kim<sup>2</sup>, Sang Yeol Lee<sup>1</sup>  
<sup>1</sup>*Korea Institute of Science and Technology, Korea*, <sup>2</sup>*Korea University, Korea*
- TF1300 Characteristics of Indium-tin-oxide Thin Films Deposited by e-beam Evaporator at High Temperature**  
Su-Chang Ahn, Hyun-jun Choi, Sang-Muk Kim, Jin-Hong Lee  
*Korea Photonics Technology Institute, Korea*
- TF1252 The Effect of Magnesium Oxide Passivation on the Bias Instability of Amorphous HfInZnO Thin Film Transistors**  
Dong Youn Yoo<sup>1,2</sup>, Do Hyung Kim<sup>1</sup>, Byeong Kwon Ju<sup>2</sup>, Sang Yeol Lee<sup>1,2</sup>  
<sup>1</sup>*Korea Institute of Science and Technology, Korea*, <sup>2</sup>*Korea University, Korea*
- TF1250 Resistivity Tailoring of Non-stoichiometric Nickel Oxide Thin Films Deposited RF-magnetron Sputtering for Application to p-channel Thin Film Transistors**  
Seung-Jun Lee<sup>1</sup>, Seongpil Chang<sup>1</sup>, Jung Ho Park<sup>1</sup>, Shin Woo Jeong<sup>1</sup>, Kyoungchul Jo<sup>1</sup>, Jong-Woo Kim<sup>1</sup>, Tae-Yeon<sup>1</sup>, Sarah Eunkyung Kim<sup>2</sup>, Byeong-Kwon Ju<sup>1</sup>  
<sup>1</sup>*Korea University, Korea*, <sup>2</sup>*Seoul National University of Science & Technology, Korea*
- TF1244 Fully Room Temperature Fabricated Pt/Y<sub>2</sub>O<sub>3</sub>/Pt Nonvolatile Memory**  
Jong-Woo Kim<sup>1</sup>, Seongpil Chang<sup>1</sup>, Jung Ho Park<sup>1</sup>, Shin Woo Jeong<sup>1</sup>, Kyoungchul Jo<sup>1</sup>, Tae-Yeon Oh<sup>1</sup>, Seung-Jun Lee<sup>1</sup>, Jeon-Kook Lee<sup>2</sup>, Byeong-Kwon Ju<sup>1</sup>  
<sup>1</sup>*Korea University, Korea*, <sup>2</sup>*Korea Institute of Science and Technology (KIST), Korea*

- TF1242 Epitaxial Recrystallization and Luminescence of CaAl<sub>2</sub>O<sub>4</sub>:Eu<sup>2+</sup> Thin Films Prepared on Sapphire Substrates**  
 Dai-Hong Kim<sup>1</sup>, Choong Ki Lee<sup>2</sup>, Jun Seong Lee<sup>2</sup>, Seong-Hyeon Hong<sup>1</sup>, Young Jin Kim<sup>2</sup>  
<sup>1</sup>Seoul National University, Korea, <sup>2</sup>Kyonggi University, Korea
- TF1233 Electrical, Structural, and Optical Properties of Ta-In-Zn-O Thin Films Fabricated using Combinatorial Sputtering System**  
 Jae-Cheol Park, Gi-Seok Heo, Jong-Ho Lee, Ho-Sung Kim, Tae-Won Kim  
*Korea Institute of Industrial Technology, Korea*
- TF1226 Efficiency Improvement of Organic Photovoltaic with Nanopatterned Electrode by Laser Interference Lithography**  
 Tae-Yeon Oh, Shin-Woo Jeong, Jung-Ho Park, Byeong-Kwon Ju  
*Korea University, Korea*
- TF1221 Effect of Photo-Illumination on Electrical Response of Diamond Diode**  
 B. Paosawatyanyong<sup>1,2</sup>, N. Rujisamphan<sup>1</sup>, W. Banthumnavin<sup>1</sup>  
<sup>1</sup>Chulalongkorn University, Thailand, <sup>2</sup>Commission on Higher Education, Thailand
- TF1192 Threshold Voltage Properties of OFET with CuPc Active Material**  
 Ho-Shik Lee, Min-Woo Cheon, Yong-Pil Park  
*Dongshin University, Korea*
- TF1169 Fabrication of All-transparent Li<sub>0.15</sub>Ni<sub>0.85</sub>O/In-Mg<sub>0.5</sub>Zn<sub>0.5</sub>O Heterojunction Thin Film Diodes with Cubic Epitaxial Structures**  
 L. Zhuang<sup>1,2</sup>, C. H. Lau<sup>2</sup>, K. H. Wong<sup>2</sup>, B. J. Li<sup>1</sup>, X. G. Tang<sup>3</sup>  
<sup>1</sup>Sun Yat-Sen University, China, <sup>2</sup>The Hong Kong Polytechnic University, China,  
<sup>3</sup>Guangdong University of Technology, China
- TF1163 Structural and Electrical Properties of Ni-germanosilicides Formed using Pulsed KrF Laser Annealing**  
 Woong-Ki Hong, Min-Woo Seo, Kyu-Hwan Shim, Jin-Sung Kim, Chel-Jong Choi  
*Chonbuk National University, Korea*
- TF1156 Epitaxial Growth and Properties of Al<sub>x</sub>Ga<sub>1-x</sub>N Layers Grown by HVPE**  
 Ji Sun Lee<sup>1,2</sup>, Dongjin Byun<sup>1</sup>, Hae-Kon Oh<sup>3</sup>, Young Jun Choi<sup>3</sup>, Hae-Yong Lee<sup>3</sup>, Jin-Ho Kim<sup>2</sup>,  
 Tae-Young Lim<sup>2</sup>, Jonghee Hwang<sup>2</sup>  
<sup>1</sup>Korea University, Korea, <sup>2</sup>Korea Institute of Ceramic Engineering & Technology, Korea,  
<sup>3</sup>LumiGNtech Co., Korea
- TF1111 Influence of He-Ne Laser ( $\lambda=632.8$  nm) Power on Doping Profile of Indium Into Cadmium Sulfide (CdS) Thin Film and Its Characteristics**  
 Kuk Do Myung, Nam-Hoon Kim, Woo-Sun Lee  
*Chosun University, Korea*
- TF1060 Interactions between Dimethylaluminum Isopropoxide Molecules and Their Effect on Dimethylaluminum Isopropoxide Reaction with a Fully Hydrogen-terminated Si (001) Surface**  
 Dae-Hee Kim, Yeong-Cheol Kim  
*Korea University of Technology and Education, Korea*

## Thin Film Processing and Devices

- TF1058 Structure and Properties of the Mg Doped CuCrO<sub>2</sub> Transparent Conducting Thin Films Deposited by Pulsed Laser Deposition**  
Chul-Ho Bae<sup>1</sup>, Dong-Kyun Shin<sup>1</sup>, Hee-Young Lee<sup>1</sup>, Se-Jong Lee<sup>2</sup>, Jai-Yeoul Lee<sup>1</sup>  
<sup>1</sup>Yeungnam University, Korea, <sup>2</sup>Kyungsung University, Korea
- TF1042 Electrical Properties of TaInZnO Thin-film Transistor Fabricated by RF Magnetron Sputtering**  
Byeong-Yun Oh<sup>1</sup>, Young-Jun Lee<sup>1,2</sup>, Chang-Woo Hong<sup>1,3</sup>, Jae-Cheol Park<sup>1</sup>, Joo-Hyung Kim<sup>2</sup>, Yong-Sung Choi<sup>3</sup>, Gi-Seok Heo<sup>1</sup>, Tae-Won Kim<sup>1</sup>, Kwang-Young Kim<sup>1</sup>  
<sup>1</sup>Korea Institute of Industrial Technology (KITECH), Korea, <sup>2</sup>Chosun University, Korea, <sup>3</sup>Dongshin University, Korea
- TF1038 Effect of Ar/O<sub>2</sub> Ratio on Properties of Thin Yttrium-Indium-Zinc-Oxide (YZIO) Films**  
Young-Jun Lee<sup>1,2</sup>, Byeong-Yun Oh<sup>1</sup>, Jae-Cheol Park<sup>1</sup>, Kwang-Young Kim<sup>1</sup>, Joo-Hyung Kim<sup>2</sup>  
<sup>1</sup>Korea Institute of Industrial Technology, Korea, <sup>2</sup>Chosun University, Korea
- TF1034 The Effect of Annealing Treatment on Thermal Stability of AGZO Thin Films Deposited by DC Moving Magnetron Sputtering**  
Jong-Ho Kang<sup>1,2</sup>, Myung-Hyun Lee<sup>1</sup>, Young Soo Lim<sup>1</sup>, Won-Seon Seo<sup>1</sup>, Mun Gi Park<sup>3</sup>, Heon-Jin Choi<sup>2</sup>  
<sup>1</sup>Korea Institute of Ceramic Engineering and Technology, Korea, <sup>2</sup>Yonsei University, Korea, <sup>3</sup>LG Display Co., Ltd, Korea
- TF988 Effects of Wavelengths on Diffraction Efficiency of As<sub>2</sub>Se<sub>3</sub> Glass Films**  
Ki-Hyun Nam, Jang-Han Kim, Hong-Bay Chung  
Kwangwoon University, Korea
- TF986 Sb-doped Effect of Ag/Ge-Se-Te Thin Films Application for PRAM**  
Ki-Hyun Nam, Hong-Bay Chung  
Kwangwoon University, Korea
- TF984 Characteristics of an Ag-inserted Amorphous InGaO<sub>x</sub>(ZnO)<sub>1-x</sub> Multilayer Films for Transparent Electrode**  
Do Yun Hwang, Jeong Hwan Lee, Han Jae Shin, Dong Cheul Han, Do Kyung Lee  
Gumi Electronics and Information Technology Research Institute, Korea
- TF979 Field Effect Characteristics in an Amorphous Ge-Se based Thin Film Transistor**  
Jang-Han Kim, Ki-Hyun Nam, Won-Ju Cho, Hong-Bay Chung  
Kwangwoon University, Korea
- TF977 Electrical Characteristics of Ag-doped Ge<sub>x</sub>Se<sub>100-x</sub> Multi-layer Cells for ReRAM Applications**  
Jang-Han Kim, Ki-Hyun Nam, Hong-Bay Chung  
Kwangwoon University, Korea

- TF967 The Properties of Transparent Conductive Indium Zinc Tin Oxide Thin Films for Dye-sensitized Solar Cell Application**  
 Hong-Chan Ma, Damisih, Jong-Hun Cheon, Jae-Hong Kim, Hee-Young Lee  
*Yeungnam University, Korea*
- TF964 Fabrication and Characterization of Sol-gel Processed InSnGeO Thin Film Transistor**  
 Jun Hyuk Choi, Soo Min Hwang, Seung Muk Lee, Guen Chul Park, Ji Cheol Kim, Jinho Joo  
*Sungkyunkwan University, Korea*
- TF946 Mg-doped ZnO Thin Film Transistors by a Solution-based Process**  
 Ji-young Oh<sup>1</sup>, Musarrat Hasan<sup>2</sup>, Sang Chul Lim<sup>1</sup>, Seung-Youl Kang<sup>1</sup>, Chul-Am Kim<sup>1</sup>, Jonghyuk Park<sup>1</sup>, Sang Seok Lee<sup>1</sup>, Hongki Cha<sup>1</sup>, Kyoung Soo Suh<sup>1</sup>, Kyoung Ik Cho<sup>1</sup>, Seong Deok Ahn<sup>1</sup>  
<sup>1</sup>ETRI, Korea, <sup>2</sup>Inha university, Korea
- TF907 Properties of IZTO Transparent Conducting Thin Films Fabricated by Magnetron Sputtering Equipped with Ion Beam System**  
 Se-Jong Lee<sup>1</sup>, Jai -Youl Lee<sup>2</sup>, Nam-In Cho<sup>3</sup>  
<sup>1</sup>Kyungsung University, Korea, <sup>2</sup>Youngnam University, Korea, <sup>3</sup>Sunmoon University, Korea
- TF879 Flexible Thin Film Transistor with Organic Gate Insulator and IGZO as the Active Layer**  
 Heeok Kim, Hongki Cha, Seungyoul Kang, Sangchul Lim, Seongdeok Ahn, Kyoungik Cho  
*ETRI, Korea*
- TF1676 Fabrication of IZO Thin Films for Flexible Organic Light-emitting Diodes by RF Magnetron Sputtering**  
 Dae-guen Jun, Hyun-hong Cho, Dam-bi Jo, Kyu-Mann Lee  
*Korea University of Technology and Education, Korea*

Nov. 10, 2011 (Thu.)

**TFP 2 (Thin Film Processing and Devices) Poster Presentation 2**

Lobby 8F

Chair: Prof. Zonghoon Lee (Ulsan National Institute of Science and Technology, Korea ) 13:30-15:00

- TF347 Effect of Processing Parameters on Properties of ZnO Film Deposited by DC Reactive Magnetron Sputtering Method**  
 Chan-Soo Baek<sup>1</sup>, Do Hyung Kim<sup>2</sup>, Sang Yeol Lee<sup>2</sup>, Hyun-Hoo Kim<sup>3</sup>, Kee-Joe Lim<sup>1</sup>  
<sup>1</sup>Chungbuk National University, Korea, <sup>2</sup>Korea Institute of Science and Technology, Korea, <sup>3</sup>Doowon Technical College, Korea
- TF1146 Fabrication and Electrical Characteristics of Graphene Coated Copper Substrate by Electro Spray Coating Method**  
 Jungsoo Kim, Hyung-Ho Jo, Dae-Guen Nam  
*Korea Institute of Industrial Technology, Korea*

## Thin Film Processing and Devices

- TF877 The Electrical Properties of Fabricated Hybrid Structure for using Digital X-ray Detector**  
Jung-Wook Shin, Kyung-Min Oh, Hye-Jin Park, Ji-Yun Lee, Kyoung-Jun Yoon, Sang-Hee Nam  
*Inje University, Korea*
- TF855 Study on Microstructure and Dielectric Properties of Sol-gel-processed ZrO<sub>2</sub> Films with Different Heat Treatment Time**  
Seung Muk Lee, Soo Min Hwang, Jun Hyuk Choi, Geun Chul Park, Ji Cheol Kim, Jinho Joo  
*Sungkyunkwan University, Korea*
- TF851 Microstructural Change of Solution-Processed ZrO<sub>2</sub>/Si Films by Thermal Annealing**  
Soo Min Hwang, Jun Hyuk Choi, Seung Muk Lee, Geun Chul Park, Ji Cheol Kim, Jinho Joo  
*Sungkyunkwan University, Korea*
- TF842 Wet Chemical Etching Properties of Transparent Zn and Sn Co-doped In<sub>2</sub>O<sub>3</sub> Electrode for Flexible Electronics Applications**  
Han Jae Shin, Dong Cheul Han, Do Kyung Lee  
*Gumi Electronics and Information Technology Research Institute, Korea*
- TF833 The Feasibility Study of Avalanche Photoconductor in Digital Radiography**  
Jung-Wook Shin, Kyung-Min Oh, Sung-Hun Kim, Yoon-Jin Lee, Kyu-Hong Lee, Sang-Hee Nam  
*Inje University, Korea*
- TF818 UV-shielding and Hydrophilic Protective Films Containing TiO<sub>2</sub>@SiO<sub>2</sub> Nanoparticles**  
Hyeong Seok Lee<sup>1,2</sup>, Se Mi Im<sup>1,3</sup>, Jung Whan Yoo<sup>1</sup>  
<sup>1</sup>Korea Institute of Ceramic Engineering and Technology, Korea, <sup>2</sup>Hanyang University, Korea, <sup>3</sup>Inha University, Korea
- TF796 Fabrication and Characteristics of ZnO Nanorods Grown on Zinc Foil by Chemical Bath Deposition**  
Ji Hye Sung<sup>1,2</sup>, Jin-Ho Kim<sup>1</sup>, Jonghee Hwang<sup>1</sup>, Tae-Young Lim<sup>1</sup>, Yong Soo Cho<sup>2</sup>  
<sup>1</sup>Korea Institute of Ceramic Engineering and Technology, Korea, <sup>2</sup>Yonsei University, Korea
- TF792 Schottky Diode with Ag, Au, Pd, and Ni on ZnO/MgZnO Heterostructure**  
Jong-Hoon Lee<sup>1</sup>, Chang-Hoi Kim<sup>1</sup>, Ah-Ra Kim<sup>1</sup>, Hong-Seung Kim<sup>1</sup>, Nak-Won Jang<sup>1</sup>, Young Yun<sup>1</sup>, Min-Wook Pin<sup>2</sup>, Won-Jae Lee<sup>2</sup>  
<sup>1</sup>Korea Maritime University, Korea, <sup>2</sup>Dong-Eui University, Korea
- TF767 Effect of Bottom Layer Thickness on Crystalline Quality and Surface Roughness of ZnO Film Prepared by Multi-step Deposition Process**  
Du-Han Bae, Won-Jae Lee, Geun-Hyoun Lee  
*Dong-Eui University, Korea*

- TF766 Dielectric Properties of the Sol-gel-deposited Ultra-thin  $Gd_2O_3$  Films with Different Sintering Temperatures**  
 Myung Soo Lee, Hyoungsub Kim  
*Sungkyunkwan University, Korea*
- TF765 Gas Permeability of Carbon/ $SiO_2/Al_2O_3$  Membrane Fabricated by Plasma-enhanced Chemical Vapor Deposition**  
 Jin-Soo Jeong<sup>1</sup>, Churl-Hee Cho<sup>2</sup>, Jong-Oh Kim<sup>1</sup>, Won Youl Choi<sup>1†</sup>  
<sup>1</sup>*Gangneung-Wonju National University, Korea*, <sup>2</sup>*Korea Institute of Energy Research, Korea*
- TF690 Microstructure Analysis of DLC Thin Film Fabricated by Filtered Arc Ion Plating Method**  
 Min-Woo Cheon<sup>1</sup>, Tae-Gon Kim<sup>2</sup>, Ho-Shik Lee<sup>1</sup>, Yong-Pil Park<sup>1</sup>  
<sup>1</sup>*Dongshin University, Korea*, <sup>2</sup>*Dongshin University Graduate School, Korea*
- TF686 Characteristics of Rhenium-Iridium Coating Thin Film on Tungsten Carbide by Multi-target Sputter**  
 Min-Woo Cheon<sup>1</sup>, Tae-Gon Kim<sup>2</sup>, Ho-Shik Lee<sup>1</sup>, Yong-Pil Park<sup>1</sup>  
<sup>1</sup>*Dongshin University, Korea*, <sup>2</sup>*Dongshin University Graduate School, Korea*
- TF676 Au/Ti Ohmic Contacts to Pulsed-laser Deposited ZnO Layer on p-type SiC**  
 Ji-Chul Jung<sup>1</sup>, Min-Seok Kang<sup>1</sup>, Ji-Hong Kim<sup>2</sup>, Kang-Min Do<sup>2</sup>, Byung-Moo Moon<sup>2</sup>, Sung-Jae Joo<sup>3</sup>, Wook Bahng<sup>3</sup>, Sang-Cheol Kim<sup>3</sup>, Nam-Kyun Kim<sup>3</sup>, Ji-Hoon Lee<sup>1</sup>, Sang-Mo Koo<sup>1</sup>  
<sup>1</sup>*Kwangwoon Univ., Korea*, <sup>2</sup>*Korea Univ., Korea*, <sup>3</sup>*Korea Electrotechnology Research Institute, Korea*
- TF660 Feasibility Study of Multi-layered Flexible ITO Electrode Substrate Fabricated by Roll-to-roll Sputtering System to Apply for Medical Image Sensor**  
 Sung-Hun Kim, Jung-Wook Shin, Kyung-Min Oh, Ji-Na Kim, Seung-Uk Heo, Sang-Hee Nam  
*Inje University, Korea*
- TF635 Effects of Liquid Crystal Alignment on Molybdenum Oxide ( $MoO_3$ ) via Ion Beam Irradiation Angle**  
 Jong-Jin Lee, Hyung-Jun Kim, Gun-Young Lee, Hong-Gyu Park, Byoung-Yong Kim, Dae-Shik Seo  
*Yonsei University, Korea*
- TF632 Transparent Conductive Carbon Nanotube Network Films for Liquid Crystal Displays**  
 Hong-Gyu Park<sup>1</sup>, Min-Ji Lee<sup>1,2</sup>, Dae-Shik Seo<sup>1</sup>  
<sup>1</sup>*Yonsei University, Korea*, <sup>2</sup>*Korea Electronics Technology Institute, Korea*
- TF611 Comparative Study between ENIG and ENEPIG Soldering with Low Ag Content Sn-Ag Solder**  
 Jeong-Won Yoon<sup>1</sup>, Jong-Gun Lee<sup>1</sup>, Young-Chul Lee<sup>1</sup>, Bo-In Noh<sup>1,2</sup>, Seung-Boo Jung<sup>1</sup>  
<sup>1</sup>*Sungkyunkwan University, Korea*, <sup>2</sup>*Samsung Electronics Co., Ltd., Korea*

## Thin Film Processing and Devices

- TF602 Contact-dimension-dependent Electrical Conductivity of Graphite Powders, Carbon Nanotubes, and Exfoliated Carbon Nanosheets Under Physical Pressures**  
Sung-Ho Choi, Hye-Mi Ju, Kwang Yeon Cho, Jihoon Kim, Seung Hun Huh  
*KICET, Korea*
- TF597 Novel Partially Depleted SOI MOSFETs for Reducing the Floating-body Effect**  
Abdollah Abbasi, Ali A. Orouji  
*Semnan University, Iran*
- TF592 Structural and Electrical Characterizations of n-Type  $\beta$ -FeSi<sub>2</sub>/p-Type Si Heterojunctions Fabricated by Facing-Targets Direct-Current Sputtering**  
Nathaporn Promros, Kyohei Yamashita, Shota Izumi, Tsuyoshi Yoshitake  
*Kyushu Univ., Japan*
- TF591 Evaluation of n-Type Nanocrystalline FeSi<sub>2</sub>/p-type Si Heterojunctions Prepared by Pulsed Laser Deposition as Near-infrared Photodetectors**  
Nathaporn Promros, Li Chen, Tsuyoshi Yoshitake  
*Kyushu Univ., Japan*
- TF590 Effects of Carbon-doping on Electrical Properties of n-type Nanocrystalline FeSi<sub>2</sub>/p-type Si Heterojunction Photodiodes Prepared by Pulsed Laser Deposition**  
Nathaporn Promros, Chen Li, Tsuyoshi Yoshitake  
*Kyushu Univ., Japan*
- TF589 Improved Breakdown Voltage of SOI MESFET with 4H-SiC Layer**  
Ali. A. Oruji, Masoomeh Ghasemian, Amirhossein Aminbeidokhti, Soude Rahmaninezhad  
*Semnan University, Iran*
- TF570 Synthesis and Optical Properties of Thermochromic Vanadium Oxide Thin Films by RF Magnetron Sputtering**  
Seung Ho Han<sup>1</sup>, Hyun Bin Kim<sup>2</sup>, Dong-gun Moon<sup>2</sup>, Hyeung-Gyu Lee<sup>1</sup>, Woo Seok Yang<sup>1</sup>  
<sup>1</sup>*Korea Electronics Technology Institute, Korea*, <sup>2</sup>*Samsung Corning Precision Materials, Korea*
- TF528 Electrochemical Characteristics of Electrochromic Devices with Fluorine Doped Tin Oxide as Transparent Electrode**  
Jihun Park<sup>1,2</sup>, Chairul Hudaya<sup>1,3</sup>, Dongjin Byun<sup>2</sup>, Joong Kee Lee<sup>1</sup>  
<sup>1</sup>*Korea Institute of Science and Technology, Korea*, <sup>2</sup>*Korea University, Korea*, <sup>3</sup>*University of Science and Technology, Korea*
- TF492 Improved Characteristics SOI MOSFETs with Two New Structures: Raised Buried Oxide and Recessed Buried Oxide**  
Ali A. Orouji, Soude Rahmaninezhad, Amirhossein Aminbeidokhti, Masoomeh Ghasemian  
*Semnan University, Iran*

- TF475 Novel Structure of Polycrystalline Silicon Thin-Films Transistor with Controlled Crystal Orientation**  
 Min-Sun Kim<sup>1</sup>, Hyun Min Cho<sup>1</sup>, Seung Ki Joo<sup>2</sup>  
<sup>1</sup>Korea Electronics Technology Institute, Korea, <sup>2</sup>Seoul National University, Korea
- TF428 Fabrication of Multi-color Photochromic Thin-film**  
 Bonghoon Kang<sup>1</sup>, Dongsoo Choi<sup>1</sup>, Gi-Tae Joo<sup>2</sup>  
<sup>1</sup>Far East University, Korea, <sup>2</sup>Seoul National University of Technology, Korea
- TF424 Effect of Optimized Ti/Al/Ta/Au Ohmic Contact Resistance and Surface Morphology in AlGaN/GaN HEMTs**  
 S.J. Cho, C. Wang, N.Y. Kim  
 Kwangwoon University, Korea
- TF411 Development and Post Annealing Influence on Chemical and Physical Properties of Cost Effective Nanostructure ZIO Thin Films**  
 Vipin Kumar Jain<sup>1</sup>, Praveen Kumar<sup>2</sup>, Subodh Srivastav<sup>3</sup>, Y.K. Vijay<sup>3</sup>  
<sup>1</sup>JK Lakshmi pat University, India, <sup>2</sup>National Physical Laboratory, India, <sup>3</sup>University of Rajasthan, India
- TF388 Contribution of Oxygen Working Pressures Investigated Over a Narrow Range to TiO<sub>2</sub> Thin-film Properties in Pulsed Laser Deposition**  
 Min-Wook Pin<sup>1</sup>, Geun-Hyoung Lee<sup>1</sup>, Won-Jae Lee<sup>1</sup>, Eun-Ho Choi<sup>2</sup>, Young-Zo Yoo<sup>2</sup>  
<sup>1</sup>Dong-Eui University, Korea, <sup>2</sup>Samsung Corning Precision Materials, Korea
- TF385 The Effects of High-energy Electron Beam Irradiation on the Properties of IGZO Thin Films Prepared by rf Magnetron Sputtering**  
 So Hyun Jung<sup>1</sup>, Hye Ji Moon<sup>1</sup>, Min Ki Ryu<sup>2</sup>, Kyoung Ik Cho<sup>2</sup>, Byung Seong Bae<sup>1</sup>, Eui-Jung Yun<sup>1</sup>  
<sup>1</sup>Hoseo University, Korea, <sup>2</sup>ETRI, Korea
- TF374 Alternative Indium-Free Material for Electric Vehicle Window Transparent Heater**  
 Chairul Hudaya<sup>1,2</sup>, Ji Hun Park<sup>1,3</sup>, Joong Kee Lee<sup>1</sup>  
<sup>1</sup>Korea Institute of Science and Technology, Korea, <sup>2</sup>University of Science and Technology, Korea, <sup>3</sup>Korea University, Korea
- TF264 A Direct Monitoring of Four-bit/Cell Operation using Two-step Pulse Program Method**  
 Ho-Myoung An<sup>1</sup>, Byungcheul Kim<sup>2</sup>, Tea Geun Kim<sup>1</sup>  
<sup>1</sup>Korea University, Korea, <sup>2</sup>Jinju National University, Korea
- TF233 Characterization and Optimization of P-type Gallium Tin Oxide (GTO) Thin Films Prepared by RF Magnetron Sputtering**  
 Ferdyano Finanda, Damisih, Hong Chan Ma, Hee Young Lee  
 Yeungnam University, Korea
- TF211 Effect of Oxygen Concentration on Electrical and Physical Characteristics of Sodium Potassium Niobates Ferroelectric Thin Films**  
 Jen-Hwan Tsai<sup>1</sup>, Kai-Huang Chen<sup>2</sup>, Chien-Min Cheng<sup>2</sup>, Chun-Cheng Lin<sup>1</sup>  
<sup>1</sup>Chinese Air Force Academy, Taiwan, <sup>2</sup>Tung-Fang Design University, Taiwan, <sup>3</sup>Southern Taiwan University, Taiwan

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- TF209 Fabrication and Electrical Characterizations of CuO Thin Films for Applications in Resistive Random Access Memory Devices**  
Chien-Min Cheng<sup>1</sup>, Kai-Huang Chen<sup>2</sup>, Jen-Hwan Tsai<sup>3</sup>, Chun-Cheng Lin<sup>3</sup>  
<sup>1</sup>*Southern Taiwan University, Taiwan*, <sup>2</sup>*Tung-Fang Design University, Taiwan*, <sup>3</sup>*Chinese Air Force Academy, Taiwan*
- TF200 Double Step Insulator Fin Field Effect Transistor**  
Mahsa Mehrad, Ali A. Orouji  
*Semnan University, Iran*
- TF186 Investigation of CuInS<sub>2</sub> Absorber Layer Prospered by Sulfurization of Cu-In Precursor used by DC/RF Magnetron Sputtering**  
Hyeon Hun Yang<sup>1</sup>, Suk-Ho Lee<sup>2</sup>, Gye-Choon Park<sup>1</sup>, Jin Lee<sup>1</sup>  
<sup>1</sup>*Mokpo National University, Korea*, <sup>2</sup>*Southwestern Research Institute of Green Energy Technology, Korea*
- TF168 A Novel Structure for Leakage Current Improvement: A Triple Gate Poly Silicon Thin Film Transistor with Non Uniform Doping Channel**  
Ali A. Orouji, Robabeh Esmailnezhad  
*Semnan University, Iran*
- TF118 Investigation of Cu-Ag Film Electrodeposited in Cyanide-based Electrolyte**  
Sang Heon Yong<sup>1</sup>, Myung Jun Kim<sup>2</sup>, Jae Jeong Kim<sup>2</sup>, Jun Young Park<sup>1</sup>, Oh Joong Kwon<sup>1</sup>  
<sup>1</sup>*University of Incheon, Korea*, <sup>2</sup>*Seoul National University, Korea*
- TF105 Optical and Electrical Properties of Two-Step Grown Naturally Textured AZO Transparent Conducting Oxide Layer**  
Mandal Kankan Prosad<sup>1,2</sup>, Moo Yeol Kim<sup>1,2</sup>, Jong Ho Lee<sup>1</sup>, Bum Ho Choi<sup>1</sup>, Dong Chan Shin<sup>2</sup>  
<sup>1</sup>*Korea Institute of Industrial Technology, Korea*, <sup>2</sup>*Chosun University, Korea*
- TF103 Thermal Stability of 3 nm Thick Ir Layer Prepared by Hybrid Atomic Layer Deposition**  
Moo Ryul Kim<sup>1,2</sup>, Kankan Proaad Mandal<sup>1,2</sup>, Jong Ho Lee<sup>1</sup>, Bum Ho Choi<sup>1</sup>, Dong Chan Shin<sup>2</sup>  
<sup>1</sup>*Korea Institute of Industrial Technology, Korea*, <sup>2</sup>*Chosun University, Korea*
- TF95 Structural and Electrical Properties of Chemical Solution Deposited NiFe<sub>2</sub>O<sub>4</sub> Thin Films**  
H. J. Kim, J. W. Kim, S. S. Kim, G. H. Kim, Y. R. Bae, E. S. Kim, C. M. Raghavan, D. Do, M. H. Lee, Tae Kwon Song, Y. S. Sung, M. H. Kim  
*Changwon National University, Korea*
- TF903 A Study of Stacked Buffer Layer for the Epitaxial Growth of Zn<sub>0.5</sub>Mg<sub>0.5</sub>O Films on c-sapphire by Pulsed Laser Deposition**  
Chang-Hoi Kim<sup>1</sup>, Jong-Hoon Lee<sup>1</sup>, Hong-Seung Kim<sup>1</sup>, Min-Wook Pin<sup>2</sup>, Won-Jae Lee<sup>2</sup>, Nak-Won Jang<sup>1</sup>, Young Yun<sup>1</sup>  
<sup>1</sup>*Korea Maritime University, Korea*, <sup>2</sup>*Dong Eui University, Korea*